

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	TAMURA, K. et al.
Appl. No.	:	10/560,126
Filed	:	August 28, 2006
For	:	POSITIVE RESIST COMPOSITION, RESIST LAMINATES AND PROCESS FOR FORMING RESIST PATTERNS
Examiner	:	C. Hamilton
Group Art Unit	:	1752

SECOND PRELIMINARY AMENDMENT**Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.